PATENT	NUMBER	and
199	HE DATE	

U.S. UTILITY Patent Application

在南外中的特殊的社会。

APPL NUM	FILING DATE	CLASS	SUBCLASS	GAU	EXAMINER	
10005803	12/05/2001	438),	1765	n(n)	
**APPLICANT	S: Shih Hs	sin-Ching:	Su ien _	Li-Te	e, Chiao Li-Chie.	
**CONTINUIN	G DATA VERIFIEI	D:				
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** FOREIGN	APPLICATIONS V	ERIFIED:	:			
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Foreign priority of	aimed	<i>⊒</i> 7€	es il no es il no		ATTORNEY DOCKET NO	
35 USC 119 cond Verified and Ackn	ncons met rowiedged Examinersis		es 🚅 .10		TS01 663	
TITLE : Dry-w	et-dry solvent-free	process a	after stop layer	etch ir	n dual damascene process	<u>.</u>
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NOTICE OF ALL	WANCE MAILED	CLAIMS ALLOWED					
		Assistant Examiner	Total Claims		Print Claim for O.G		
ISSUE FEE				DRAWING			
Amount Due Date Paid	1	Sheets Drwg.	Figs.Drwg.	Print Fig.			
		Primary Examine					
TER	RMINAL	PREPARED FOR ISSUE	Application Examiner				
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